Thermal and Power Challenges in High Performance Computing Systems

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ABSTRACT

This paper provides an overview of the thermal and power challenges in emerging high performance computing platforms. The advent of new sophisticated applications in highly diverse areas such as health, education, finance, entertainment etc. is driving the platform and device requirements for future systems. The key ingredients of future platforms are vertically integrated (3D) die-stacked devices which provide the required performance characteristics with the associated form factor advantages. Two of the major challenges to the design of TSV-based (through-silicon-via) 3D stacked technologies are (i) effective thermal management and (ii) efficient power delivery mechanisms. Some of the key challenges that are articulated in this paper include hot-spot superposition and intensification in a 3D stack, design/optimization of TTSVs (Thermal Through Silicon Vias), non-uniform power loading of multi-die stacks, efficient on-chip power delivery, minimization of electrical hotspots etc.

1. INTRODUCTION

Emerging trends in processor technology has led to the rapid development of highly advanced and powerful computers with capabilities that far surpass those of current machines. At the very centre of these high performance computers are multi-core processors which have anywhere between tens to hundreds of computational cores in the silicon. This is a phenomenal leap forward in the computational performance of the processor from those of existing products which offer approximately 4-8 cores in the silicon. This giant leap in performance is driven by a number of emerging software applications such as real-time data mining, artificial intelligence, turbulence modeling, genetic engineering etc. High performance computing, also known as Terascale Computing, has made it possible to generate, process, investigate and create large amounts of data for all kinds of diverse applications. The current paper describes the different challenges and research opportunities in the field of high performance computing.

As evidenced by Moore’s law, transistor feature sizes are continually reducing at about 0.7X in linear dimensions per generation which enables a 2X increase in transistor density. This enables the number of transistors in a piece of silicon to exceed beyond 10 billion for the same footprint. Lithography has thus made it possible for the industry to create chips with many cores that can execute several thousand tasks in parallel.

Some of the future terascale applications include advanced modeling of fluid physics (wave modeling), advanced gaming systems (virtual reality), real-time data mining, real-time financial model analysis/development, computer vision and personal entertainment systems such as video karaoke. All these applications require high performance, high bandwidth and high computational power.

2. 3D STACKING TECHNOLOGY - KEY INGREDIENT OF FUTURE HIGH PERFORMANCE COMPUTING PLATFORMS

The key physical computational ingredients of HPC platforms are vertically stacked device technologies (also known as 3D stacked devices). Herein the devices are stacked on atop the other either as package stacking or die-stacking (Figure 1). Stacking offers tremendous performance advantages in the same volumetric space as a single chip scale package.
In the case of wire-bonded and package stacks, the process of manufacturing stacked devices is mature and reliable. The big challenge in the industry today is that of developing Through-Silicon-Via (TSV)-based stacking technologies. In this technology, the through vias are created through the different dies that are stacked. These through vias are used as interconnects for signal, power and thermal reasons. Figure 2 schematically shows a die-stack with TSVs.

Stacked packages are finding applications in the entire spectrum of platforms: from high-end servers to commercial desktops to mobility products. Common applications of stacked packages include high performance memory including DRAM and flash memory, logic-memory stack, system in a package or SIP etc. For example, memory modules with stacked packages are becoming necessary due to the very high bandwidth as well as latency requirements. Integrated logic and memory (often vertically stacked) are often used in applications such as cell-phones and small form factor devices. Ultra-high workloads for servers, on the other hand, are beginning to demand extraordinary memory and computational performance and it appears that this can be met only through stacking of packages. While there is a significant amount of research work that has been done on single chip scale packages, a similar body of work needs to be performed on stacked packages. Because of the rapid evolution of the platforms with their shrinking footprints, the power densities of the packages are reaching extraordinary levels and the associated cooling requirements have become extremely significant. On the other hand, the cost constraints are constantly on the downward ramp and the industry continually strives for innovative means to employ air cooling even for higher power applications.

3. HEAT TRANSFER RESEARCH ON STACKED DEVICES – A BRIEF SUMMARY

Heat transfer research on single chip electronic packages has been ongoing for over two decades and a phenomenal amount of data and work can be found in the open literature. Since the amount of research is enormous, only some of the key research that is relevant to the present study is mentioned here. Wirtz [1] provides an excellent review of convective cooling on electronic packages. Sparrow et al. [2, 3] investigated heat transfer enhancement in package arrays and also examined effect of flow bypass on the package heat transfer. Anderson and Moffat [4] examined arrays of electronic packages to understand the effects of turbulence on the element heat transfer. Chyu and Natarajan [5, 6] have done a significant amount of work on forced convective cooling of solitary cubic elements and developed correlations for both local and average heat transfer. The Reynolds number dependencies for the average heat transfer from solitary un-stacked electronic packages are consistent with the findings of Igarashi [7, 8] and Goldstein [9] on two dimensional flow regimes around a tall cylinder/prism. There are several other studies that have focused on single chip package heat transfer and are too numerous to mention in this paper. The thermal performance of three-dimensional multi-chip modules in free convection is examined using both computational and experimental methods by Chen et. al. [10]. The development of advanced thermal resistance models for stacked packages is the focus of the work done by Im and Banerjee [11]. There is a major effort to investigate 3-D stacking thermal phenomena by Agonafer et al. and in their recent work [12], the reliability of stacked packages and associate thermal issues are studied. An interesting study of the application of pulsating heat pipes to three-dimensional stacked electronic modules is performed by Khandekar et al. [13]. Substrate enhancement techniques have been looked at by Sienski et al. [14]. Recently, there was a detailed analysis of the thermal characteristics of a stacked electronic package (P-O-P) by Natarajan [15]. In this work, rules of estimation were developed for different P-O-P and die-stacked configurations.

4. THERMAL CHALLENGES IN 3D STACKED DEVICES

As stated earlier, there is a lack of a comprehensive description of the thermal challenges for 3D stacked device technology and it is the purpose of this current paper to alleviate that need. The thermal design of a stacked package is very complex and often requires elaborate models and analyses with large design times. A number of fundamental questions pertaining to forced convective cooling of stacked packages need to be addressed. Some of these questions include: how does the thermal performance vary between stacked and single chip packages? What is the fluid dependency of stack heat transfer and does it demonstrate the same behavior as those of single chip devices? What is the effect of board conduction on the heat transfer from the different dies of a stacked package? Is there any scalability of the heat transfer data of a single chip package to that of a multi-chip stack? What are the thermo-mechanical challenges (such as TSV stress characteristics, fatigue behavior, effect of thermal cycling) of stacked devices? What are the optimization implications of TTSVs floorplanning to maximize heat flow from the stack and minimize the die temperature? What is the effect of non-uniform power dissipations (power-map) of the different dies on the cooling requirements of the stacked package?

This section describes some of the key thermal challenges in 3D stacked devices:

4.1 Hot spot intensification in a die-stack and die-to-die powermap superposition

It is well known that the amount of heat dissipated is not the only factor that determines the die operating temperature and that the non-uniform power distribution on the die has a significant impact on die temperature and the cooling strategy. In a typical processor, the non-uniformity of power (also known as powermap) reduces the allowable heat dissipation from the CPU. This is because the cooling method has to not only remove the aggregate heat load from the die but also reduce the peak temperature to the desired limit.

![Figure 3 Effect of Power Map Superposition](image)

In a 3D architecture, several devices are stacked on top of the other and the superimposition (not necessarily linear) of powermaps makes the thermal solution exceedingly challenging. In the worst
case, if the active regions or hot spots on each of the dies are arranged vertically one on top of the other, the effective power density rises several-fold giving rise to very high and impractical operating temperatures. Moreover, the interior dies are further away from the cooling interface and consequently are harder to cool. If the cooling is insufficient, then the dies that are on the interior can have a “thermal runaway” effect causing the system to freeze up or in an extreme situation, there is thermal breakdown of the device. Figure 3 shows the effect of stacking a second die on top of a single die. The stacking of the second die creates a thermal profile that is much worse than in the case without stacking.

4.2. Inner die cooling in a die-stack
In a vertically integrated stack of dies or packages, the thermal resistance to cool the interior dies is high due to the presence of a number of interfaces between the die and the cooling solution. To cool a stack, there are essentially two paths for the heat to be transferred from the interior dies; one, vertically upwards to the main thermal solution, second, downwards through the package or motherboard. In a typical CPU package, heat transfer through the base of the package in usually insignificant. However, in low power CSPs such as package-stacks (P-O-P), these effects are significant.

A recent study on thermal characteristics of package-stacks and die-stacks revealed some interesting behavior of two and four-package stacks [15]. For these studies, the motherboard was conductive and not adiabatic. In a two package stack, the temperature difference between the top die and its bottom counterpart is rather small (Figure 4 a) for a given channel-to-package aspect ratio. The same behavior is seen for a two-package-stack (Figure 4 b) even in a free convection environment [10] with the difference in heat transfer coefficient between the top and the bottom dies approximately 6%. The ratio of the temperature rise (above ambient) of the top die to that of bottom die is about 0.86. On the contrary, the thermal characteristics of four packages stacked one on top of the other are more complex and shows significant variability in between the different packages in the stack. For all the cases that are considered in the present study, the bottom-most package in a four-package stack has the lowest temperature and highest heat transfer coefficient. Further, the package with the highest temperature and lowest heat transfer coefficient is the second package from the top. The difference in heat transfer between the die with highest temperature and the one with the lowest temperature is approximately 14.4 % for high channel-to-package aspect ratio.

In general, as the number of elements in a package increases, the heat transfer coefficient reduces. Of course, the actual heat dissipation that can be sustained by a multi-package stack is higher than a single chip package. As one increases the thermal load on a package, the die temperatures in the stack rapidly approach their acceptable thermal limits and may require additional cooling relief using heat sinks etc.

The effect of board conduction on the heat transfer coefficient for a four-package stack is also substantial, as in the single chip package. As seen in the earlier studies [15], the adiabatic heat transfer coefficient of a four die stack could be as much as 40% to 60% lower than that with board conduction included. Another interesting fact regarding the adiabatic board simulation is that, the lowest performing package from a thermal point of view is the bottom-most in the four die stack. That is, the bottom-most die is thermally choked causing it to have the highest temperature in the stack.
4.4. Non-Uniform Power Loading in a Multi-Die Stack with Similar Dies

A challenging aspect in multi-die stack (P-O-P package stack) thermal design is to understand its thermal behavior for non-uniform power operating modes. In such a condition, the temperature of each die in the stack is coupled with the power loadings of other dies in the stack. To accurately develop a general model to predict the temperature of each die requires running either thermal tests or simulations of the stacked package under all projected power dissipation combinations. This is obviously a daunting task as the number of combinations of power dissipation for the individual dies in a stacked package can be innumerable. Again, this depends on the type of application of the stacked package. More importantly, such a detailed study will result in a correlation that is package-specific and has limited value.

While the prediction of the die temperature in a stacked package with non-uniform heating is a study by itself, the work by Natarajan [15] estimates the error in using the average heat transfer coefficient in package with uniform heating to a non-uniform situation. It was shown that a comparison of actual temperatures in a four package stack to that predicted by the correlation revealed errors as high as 9.2% in some cases. Translating this to an actual temperature, this can exceed 12 degrees in some cases with non-uniform power dissipation. In Figure 6, the temperature variation is provided for the different dies in a four stack package for a non-uniform heating profile (with the total dissipation of the package 2W). As evidenced by the graph, the temperature variation due to non-uniform heat loading is significant compared to that observed in a package with uniform thermal load on all dies.

![Figure 6 Effect of Non-Uniform Thermal Loads on the thermal profile of a Multi-Die Stack with Similar Dies](image)

4.5. Design and Optimization of Thermal-Through-Silicon-Vias (TTSVs)

Due to the ultra short lengths of the TSVs (~50-100µm), they easily overcome RC delays of long, horizontal circuit traces in conventional Multi-Chip Modules (MCM), and also provide a connection density many times that of conventional MCMs. Thus, TSVs enable a high density 3-D stacking technology. However, there are several thermo-mechanical challenges in design and planning of TSVs. The TSVs are good conductors of heat, and hence they are effective in dissipating some of the heat generated by the devices. However, the number, density and size of Signal TSVs may not be enough to provide sufficient heat paths, and therefore, dedicated Thermal-Through-Silicon-Vias (TTSVs) are required to provide additional heat dissipation paths [16]. TTSVs can be bigger in diameter (about 50 micron) and deeper (100 microns to 200 microns) than the signal TSVs.

The TTSVs are usually vias filled with Copper. Copper has a Coefficient of Thermal Expansion (CTE) of 16 x 10^{-6}/°C, whereas silicon has a CTE of about 2.6 x 10^{-6}/°C. This mismatch between the CTEs of copper and silicon can cause significant stresses near the ends of the via. If the vias are not properly designed, then the extra expansion of copper can result in cracking of Inter-Layer Dielectric (ILD) and/or silicon. A detailed study of this effect is presented in [17]. The CTE mismatch is not only a problem in normal operation of the devices, but it is also a significant, and more severe, problem during the via processing, when the via temperatures can reach as high as 400 °C. For example, [17] states that thermo-mechanical modeling of a 50 µm diameter, 200 µm deep, fully plated Cu via shows that the Cu can expand upward by 0.35 µm at the center of the via upon repeated thermal cycling during CMOS processing. For better thermal performance, the thickness of the vias must be as high as possible. However, higher thickness of the vias leads to higher thermo-mechanical stresses due to the CTE mismatch problem. One solution to accommodate thick thermal vias without causing high stresses is to fill a significant portion of the via by some other material that has a CTE closer to that of silicon. Tungsten (CTE of 4.5 x 10^{-6}/°C) and molybdenum (CTE of 4.8 x 10^{-6}/°C) are suitable for this purpose. Some of the processes by which these materials can be filled in the copper plated vias are described in [17].

Challenges in TTSV design often lead to design trade-offs, for example, the trade-off between the thermal performance of the via and the structural advantages of filling the via with tungsten, which causes degradation of thermal performance. Designing in view of these trade-offs requires sophisticated design and optimization strategies. The literature demonstrates some interesting optimization techniques used to solve design problems associated with through silicon vias. Two specific design challenges and their optimization strategies are given below.

4.5.1 Minimizing the number TTSVs: TTSVs provide effective thermal paths between the devices. However, they take up valuable silicon chip area and also put additional constraints on signal routing. Therefore, it is necessary to keep the number of TTSVs to minimum required to provide sufficient heat path. The placement of TTSVs has a significant impact on the number of TTSVs required, and an optimal placement strategy must be used in order to minimize the number of TTSVs. One such optimization strategy is presented in [16]. They formulated and solved a constrained Non-Linear Programming (NLP) problem, with the objective function being to minimize the number of TTSVs. To model the thermal performance of the via, they used a compact resistive thermal model. A thermal-driven multilevel routing algorithm is presented in [18]. Their algorithm integrates thermal via planning and signal via planning into single multilevel routing problem, and they formulate this as a min-cost flow problem, which can be solved optimally in polynomial time. They claim that using their algorithm, the number of TTSVs can be reduced 80% to achieve the same temperature, as compared to post-processing approach to insert the TTSVs.

4.5.2 Thermal-driven Floorplanning: Since thermal problems are prominent in 3-D stacked devices, it is imperative to include the thermal effects at the floorplanning stage. For example, it is important to arrange the heat generating blocks in such a way that their respective hot-spots (i.e. locations of high, localized heat dissipation) are as far away from each other as possible [19]. If devices are stacked in a way that brings the hot-spots together, it...
can have severe effect on the maximum temperature, which can increase beyond an acceptable limit. A thermal-driven
floorplanning algorithm is presented by Cong et. Al [20]. They
developed a new 3-D floorplan representation scheme and used
simulated annealing for optimization. They integrated a compact
resistive thermal model with the 3-D floorplanning algorithm.
Another algorithm for efficient thermal placement of devices is
presented in [21]. This algorithm uses a forced-directed iterative
scheme, in which thermal forces drive cells away from areas of
high temperature. They use finite element analysis to calculate
temperatures in each iteration.

4.6 Multi-disciplinary Optimization (MDO)
The design challenges described in the paper involve various
disciplines such as thermal, mechanical and electrical aspects. The
solutions exhibit inherent trade-offs between these disciplines. For
example, as described earlier, thicker TTSVs completely filled with
copper offer excellent thermal paths and help in minimizing the
peak die temperatures. However, they result in severe stresses due
to thermal expansion mismatch, and to mitigate these stresses, the
TTSVs are often filled with tungsten. This results in a decrease in
the TTSV performance as a thermal path, but increases the
reliability. Another case of the inherent trade-off between disciplines is present in the die stacking design. If the dies are
stacked in such a way that their “active cells” are aligned on top of
each other, this reduces the total wire length (which is essential to
minimize the signal delays). However, this results in hot spot
alignment and causes “thermal runaway” problems as described
earlier. If the hot spots are kept away from each other to minimize the
peak temperature, then it causes an increase in the wire length.
Sophisticated Multi-Disciplinary Optimization (MDO) techniques
are required to solve these problems. Development of the MDO
techniques, development of “fast physics” models and other
techniques to increase the efficiency of the optimization algorithms is
an active area of research in the scientific community worldwide.

5. POWER CHALLENGES IN 3D STACKING
There are key power challenges in 3D device architectures that have
an impact on the thermal behavior and performance of multi-
core CPUs. These arise from the CPU having a large number of
cores and the fact that the dies are stacked. Both these factors drive
the CPU towards demanding higher and faster currents. The challenges in power delivery to 3D die-stacking are briefly
described in this section.

5.1. Efficient on-chip power delivery for multi-core
stacked CPUs:
The trend is to reduce operating voltage in order to save power.
Subsequently, 3D devices need large currents which cause high
heat dissipations in the CPU. Unless the power distribution scheme is
optimal, the inefficiencies (I^2R loss) in the power delivery
network will result in high heat generation in overall delivery
network including package, socket and platform. The practical
realization of such a fine-grain on-chip power distribution is a huge
challenge. Even in single chip systems, the non-uniformity in
current distribution through socket pins is a problem due to
resistance differences between packages, board power planes. This
gets worse with multi-chip systems. Figure 7 schematically shows the
power losses in a power delivery network.

There are technologies that have been demonstrated which reduce
power losses by moving the voltage regulator closer to the CPU
and the 3D stack. This also reduces demand on the package level
decoupling capacitors. An overview of power distribution network
design is given in [22].

5.2. Minimization of electrical hot spots:
The fast switching and heavily active circuits cause “hot-
spots” on the die. These hot-spots are critical from a design
perspective both due to their thermal effects as well as their power
delivery impact (increases the number of decoupling capacitors
required significantly). The temperature hotspot effect has been
described earlier in detail in section 4.1.

5.3. Interconnect design for inter-die communication:
The design of the inter-die interconnects is a highly multi-
disciplinary problem and the designer needs to assess trade-offs
between thermal via requirements, die real estate availability,
interconnect requirements (such as routing length, thickness),
frequency of operation etc. In a TSV-based die-stack, the
communication between the different dies is enabled using
through-silicon-vias and the number of interconnects can easily be
in the thousands. The communication (frequency of operation,
cross-talk, noise coupling) between the different dies in the stack is
determined by the interconnect design and density. The inductance
of this inter-die connection has direct impact on the effectiveness
of package capacitors for the dies on top of the stack. The desire to
get shorter interconnects to increase frequency and reduce losses
needs to be offset by the thermal requirements for TTSVs. Again,
this trade-off needs to be examined for the particular design and is
difficult to generalize. The well-known issues of solder electro-
migration, higher thermo-mechanical stresses etc. for the first-level
interconnect for un-stacked configurations still remain even in the
current stacked architectures.

6.4. Package level decoupling:
Die to die stacking cause higher switching currents being drawn
from same package area demanding higher charge in same time.
In order to meet noise targets it becomes necessary to use faster more
expensive package capacitors. A cheaper alternative could be to
scaling number of package capacitors. But this option has two
major drawback 1) It might not be easily possible to scale number
of capacitors due to limited package real estate 2) Capacitor
effectiveness is very much dependent on their location relative to
the die location so additional capacitors might not be equally
effective due to their non ideal locations. Overall, with die stacking
it is expected to have increased demand on package level
decoupling.

6. CONCLUSIONS
This paper describes the thermal and power challenges in high
performance computing systems with specific focus on 3D die-to-
die stacked device technologies. Several challenges in the design of
cooling and power distribution for 3D architectures have been identified and described. It has been shown that the superposition of thermal powermaps significantly worsens the thermal profile and coolability of the dies in a stack. Thermal resistances for the interior dies are usually much higher than those on the extremities because of the presence of a number of interfaces between the die and the cooling solution. The designer also has to also contend with the complex design methodology for the specification of the thermal-TSVs which are critical to the overall heat removal from the stack. The minimization of TTTSV and optimal thermal floorplanning offer exciting new areas for research and innovation.

Power management for 3D stacking technology has several challenges most of which are highly coupled with the thermal behavior of the stack. High current requirements for multi-die stacks require highly efficient power delivery mechanisms with low power losses. The lack of such efficient power delivery mechanisms will result in high heat dissipation, interconnect reliability problems, electrical hot spots, reduced operating frequency etc. One of the proposed approaches that the industry is considering is to stack a voltage regulator in close proximity to the 3D stack.

The design challenges described in the paper involve various disciplines such as thermal, mechanical and electrical aspects. The solutions exhibit inherent trade-offs between these disciplines, and sophisticated multi-disciplinary optimization techniques are required to obtain optimal designs.

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